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**TITLE:** PRODUCTION OF COLOR FILTER  
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**INVENTOR-INFORMATION:**

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**ABSTRACT:**

**PROBLEM TO BE SOLVED:** To provide a color filter with a thin film black matrix having high optical density and high pattern precision by forming a polyamide resin-contg. colored resin layer on a substrate and a photosensitive resin layer on the colored resin layer.

**SOLUTION:** A colored resin layer is formed on a substrate using a

compsn. prepd. by adding a colorant to polyamide resin dissolved in a solvent. A photosensitive resin is uniformly applied on the colored resin layer and dried by heating to form a photosensitive resin layer. This photosensitive resin layer is exposed through a prescribed mask and developed with an alkaline aq. soln. At this time, only the photosensitive resin layer is patterned. The patterned photosensitive resin layer and the surfaced parts of the colored resin layer are brought into contact with an acid. The colored resin layer is then etched through the patterned photosensitive resin layer is left as a mask and finally the photosensitive resin layer is removed with a highly alkaline aq. soln. to obtain a pattern of the colored resin layer.

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